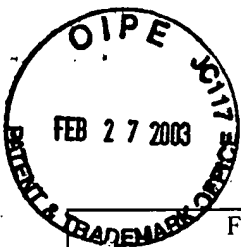




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Atty. Docket No.: 3600-328-01		Application No.: 10/042,549					
Applicant: Christopher A. MICHALUK							
Filing Date: January 9, 2002		Group Art Unit:	Not Yet Assigned				
U.S. PATENT DOCUMENTS							
Examiner Initial*		Document Number	Date	Name	Class	Sub Class	Filing Date If Appropriate
Ato	1	2,950,185	08/23/60	E.G. Hellier et al.	75	0.5	
Ato	2	3,767,456	10/23/73	Glaski	117	71 M	
Ato	3	3,829,310	08/13/74	T.X. Mahy	75	0.5 BB	
Ato	4	4,149,876	04/17/79	Rerat	75	0.5 BB	
Ato	5	4,684,399	08/04/87	Bergman et al.	75	0.5	
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Ato	9	2001/0001401	05/24/01	Segal	148	670	
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Sub Class	Translation Yes or No
Ato	10	WO 00/31310	06/02/00	WIPO	—	—	Yes
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
Ato	Kirk-Othmer, Encyclopedia of Chemical Technology, 3rd Edition, Vol. 22, pp. 541-564.						
Ato	S.I. Wright, G.T. Gray, and A.D. Rollett, <i>Textural and Microstructural Gradient Effects on the Mechanical Behavior of a Tantalum Plate</i> , <u>Metallurgical and Materials Transactions A</u> , 25A, pp. 1025-1031, 1994.						
Ato	C.A. Michaluk, R.O. Burt, and D.P. Lewis, <i>Tantalum 101: Economics and Technology of Ta Materials</i> , <u>Semiconductor International</u> , Vol. 23, No. 8, pp. 271-278, 2000.						
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Examiner				Date Considered		4/22/03	
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							
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Page 1 of 1

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Atty. Docket No.
CPM00029CIP(3600-328-01)

Application No. 10/042,549

INFORMATION DISCLOSURE STATEMENT

APPLICANT: Christopher A. MICHALUK

Filing Date: January 9, 2002

Group Art Unit: 1742

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Aio	3,497,402	2/24/70	Douglass et al.	148	11.5	
Aio	4,844,746	7/4/89	Hormann et al.	148	2	

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FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION YES NO
Aio WO 01/96620	12/20/01	WIPO	C22B		
Aio WO 99/61670	12/2/99	WIPO	C22B	34/24	
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Aio	G. I. Friedman, "Grain Size Refinement in a Tantalum Ingot", Metallurgical Transactions., vol. 2, January 1971(1971-01), pages 337-341, XP002227180 METALLURGICAL SOCIETY OF AIME. NEW YORK., US. Page 337, column 1, line 1-page 340, column 2, line 28; table 4.
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EXAMINER

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